AtOMS

by Accustrata

Atomic Spectroscopy for Advanced Thin Film Process Control

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AccuStrata

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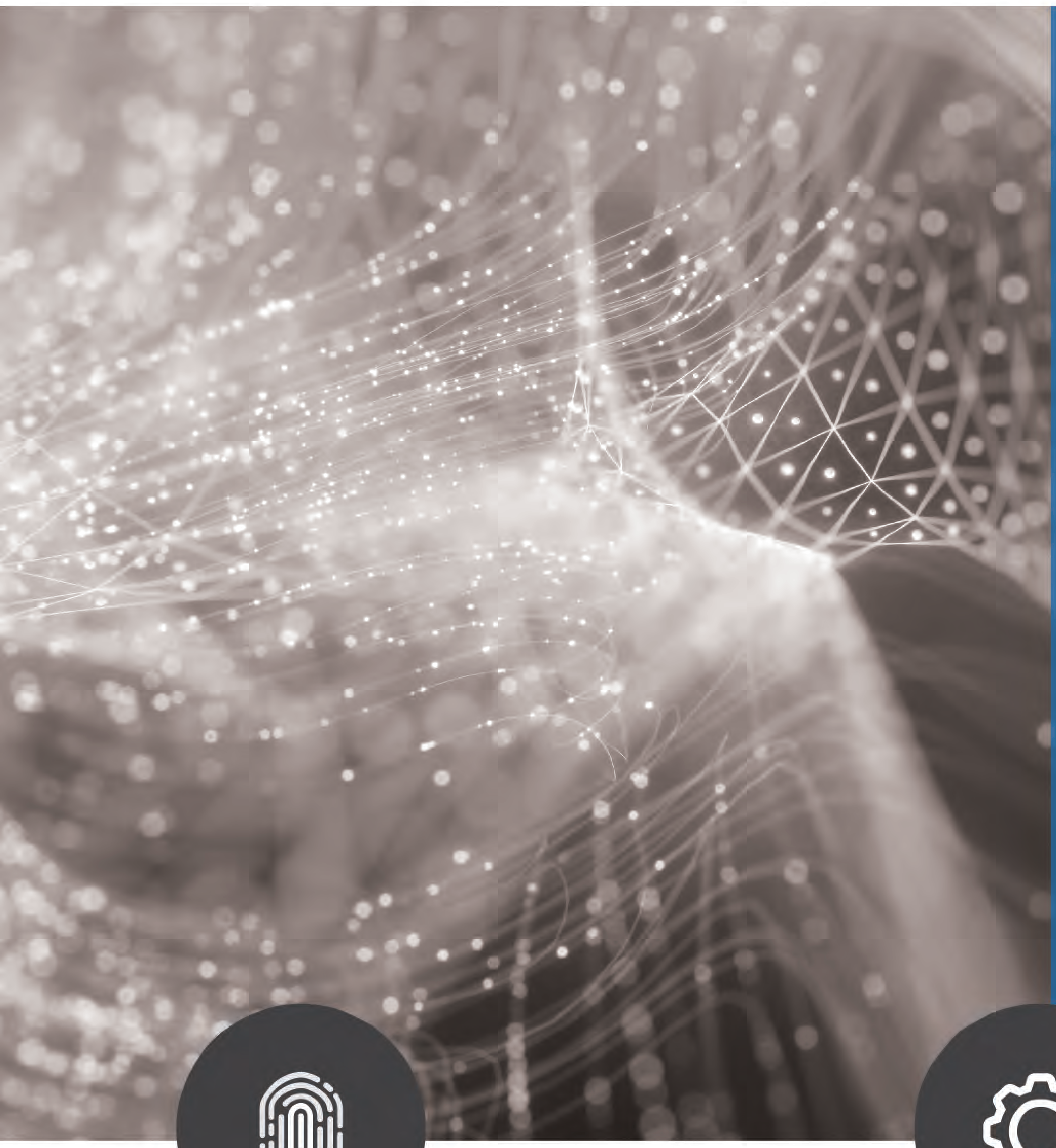

Upgrade & Expand Your Thin Film Capabilities

Advances in thin film coatings and architectures are quickly outpacing the capacities of conventional monitoring systems. AtOMS enables you to move beyond traditional methods of monitoring and process control by measuring where it matters. Establish a competitive edge in manufacturing yield, product performance, and process stability in thin film etching and deposition.

Unique

What sets AtOMS apart is our novel approach to process control. By integrating Atomic Absorption & Optical EmissionSpectroscopy (AAS & OES) with our specially engineered components, this patented system offers you capability beyond what is currently available and in cases where there is no other solution.

Customizable

A single system can monitor up to 4 elements. With over 60 elements available, we can target the unique materials you require. Three channels enable monitoring support for multi-step, multi-chamber processes or more detailed data acquisition on process uniformity in a single chamber.

Adaptive

AtOMS is designed to accommodate your existing chamber configurations and geometries. Installation versatility is facilitated by our flexible fiber optic sensors specially designed by our engineers.

The Customer

Thin Film Processes

- Physical, Plasma Etching
- Physical Vapor Deposition (PVD)

Monitoring for

- Developing & scaling up new processes
- Optimizing & stabilizing existing processes
- Transferring processes to new systems
- Increasing manufacturing yield/ throughput